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Electrochemical deposition and studies on CdCr₂S₄ thin films

T. Mahalingam^{a,*}, S. Thanikaikarasan^a, V. Dhanasekaran^a, R. Mariappan^a, P. Jayamurugan^a, S. Velumani^b, Jin-Koo Rhee^c

^a Department of Physics, Alagappa University, Karaikudi 630 003, India

^b Centro de Investigación y de Estudios Avanzados del I.P.N. (CINVESTAV), Av. Instituto Politécnico, Nacional 2508, Col. San Pedro Zacatenco, 07360 México D.F., Mexico ^c Millimeter-wave Innovation Technology Research Center, Dongguk University, Seoul 100 715, Republic of Korea

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ABSTRACT

Cadmium chromium sulphide (CdCr₂S₄) thin films have prepared on indium doped tin oxide coated conducting glass (ITO) substrates from an aqueous electrolytic bath consists of CdSO₄, Cr₂O₃ and Na₂S₂O₃ using potentiostatic electrodeposition technique. The deposited films are characterized using X-ray diffraction, scanning electron microscopy, energy dispersive analysis by X-rays and optical absorption techniques, respectively. X-ray diffraction pattern reveals that the deposited films possess polycrystalline nature with cubic structure. Surface morphology and film composition shows that the films with smooth surface and better stoichiometry are obtained under optimized deposition condition. The optical parameters such as band gap, refractive index and extinction coefficient are calculated from optical absorption measurements. The experimental observations are discussed in detail.

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1. Introduction

Thin films of diluted magnetic semiconductors attracts many researchers due to their wide range of applications in various fields [1-4]. Among them, ferromagnetic semiconductor systems have received much attention because of their applications in 'spintronics' [5,6]. CdCr₂S₄ is found to be ferromagnetic semiconductor with a band gap value 2.4 eV which have found applications in various fields [7]. Thin films of CdCr₂S₄ are usually crystallized in cubic structure (JCPDS-ICDD, 77-0677) with lattice constant (a = 10.24 Å). Berger and Pinch studied the ferromagnetic resonance of CdCr₂S₄ and CdCr₂Se₄ single crystals [8]. Berger and Ekstrom have prepared CdCr₂S₄ single crystals and studied their optical properties [9]. The preparation of CdCr₂S₄ and HgCr₂S₄ thin films by chemical bath deposition technique and their properties have been investigated by Mane et al. [10]. Salem and El-Ghazzawi have prepared $CdCr_2S_4$ thin films using chemical deposition and studied their properties [11]. Investigation of published data indicates that huge amount of literature is available about the preparation and characterization of CdCr₂S₄ single crystals but very few are available regarding thin films. Recently, electrodeposition technique appears to be attractive, due to its low cost and low temperature synthesize and the possibility to control the film thickness and morphology by readily

* Corresponding author. Tel.: +91 4565 230251. E-mail address: maha51@rediffmail.com (T. Mahalingam). adjusting the electrical parameters as well as the composition of the electrolytic solution [12–14]. The preparation of CdCr₂S₄ thin films on stainless steel substrates using electrodeposition technique and their structural, morphological, compositional and optical properties are investigated by Lade et al. [7]. To the best of our knowledge very few research reports are available concerning the growth and characterization of CdCr₂S₄ thin films [7,10,11]. Hence, we have planned to carry out systematic investigation of CdCr₂S₄ thin films obtained using electrodeposition technique. In the present work, CdCr₂S₄ thin films have prepared on indium doped tin oxide coated conducting glass (ITO) substrates from an aqueous acidic bath containing CdSO₄, Cr₂O₃ and Na₂S₂O₃. The deposited films are subjected to X-ray diffraction, scanning electron microscopy, energy dispersive analysis by X-rays and optical absorption techniques, respectively. The effect of deposition potential on structural, morphological, compositional and optical properties of the films are studied and the results are discussed.

2. Experimental details

The chemicals used in the present work were of analytical grade reagents (99.5% Purity, supplied from SD Fine, Mumbai, India). Thin films of CdCr₂S₄ were deposited on ITO substrates from an aqueous acidic bath containing 0.03 M CdSO₄, 1 M Cr₂O₃ 0.3 M Na₂S₂O₃, 0.05% H₂SO₄ and 0.05% tartaric acid using potentiostatic cathodic electrodeposition technique. The first working solution of 0.03 M CdSO₄ was obtained by dissolving 5.7714g of CdSO₄ in 250 cm³ deionized water. The second working solution of 1 M Cr₂O₃ was

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obtained by dissolving 37.9975 g of Cr₂O₃ in 250 cm³ deionized water. The third working solution of 0.3 M Na₂S₂O₃ was obtained by dissolving 18.6135 g of Na₂S₂O₃ in 250 cm³ deionized water. Initially, the pH value of the electrolytic bath was 3.5 ± 0.1 . By adding adjustable amount of NaOH the pH of the electrolytic bath was adjusted to 5.5 ± 0.1 . If the pH value is low (below 3.5 ± 0.1) there is rapid growth of films followed by its peeling out from the substrate. If the pH value is high (such as above 6.5 ± 0.1) precipitation of Na₂S₂O₃ occurs which yields films with poor quality. Hence the pH value was fixed as 5.5 ± 0.1 to deposit CdCr₂S₄ thin films. All the depositions were carried out using a PAR scanning potentiostat/galvanostat unit (Model 362, EG & G, Princeton Applied Research, USA) employing three electrode configuration with ITO substrate as working electrode, graphite plate as counter electrode and saturated calomel electrode (SCE) as reference electrode, respectively. The ITO substrates were treated for 15 min with ultrasonic waves in a bath of isopropanol and then rinsed with acetone. The SCE was kept closer to the working electrode by Luggin capillary arrangement. The pH of the electrolytic bath was maintained in the range between 3.5 and 6.5 ± 0.1 . The bath temperature and deposition time were fixed as 80 °C and 45 min, respectively. The deposition potential was fixed in the range between -550 and -850 mV versus SCE.

Thickness of the deposited films was measured using stylus profilometer (Mitutoyo SJ 301). An X-ray diffractometer (XPERTPRO PANalytical, Netherland) with CuK_{α} radiation ($\lambda = 0.1540$ nm) was used to identify the crystalline nature and phases of the deposited films. The surface morphology and film composition were analyzed using an energy dispersive analysis by X-rays set up attached with scanning electron microscope (JEOL JSM 840). Optical absorption measurements of the deposited films was recorded using an UV–Vis-NIR spectrophotometer (HR-2000, M/S Ocean Optics, USA).

3. Results and discussion

3.1. Film thickness

Thickness of the deposited films is controlled by separate variables such as (i) uniform growth (ii) surface morphology. Thickness of the deposited films is measured using stylus profilometer. By controlling the deposition potential and time, thickness of the deposited films could be controlled. Fig. 1 shows the variation of



Fig. 1. Variation of film thickness with deposition time for $CdCr_2S_4$ thin films prepared at various deposition potentials: (a) -550 mV versus SCE, (b) -650 mV versus SCE, (c) -750 mV versus SCE and (d) -850 mV versus SCE.



Fig. 2. X-ray diffraction pattern of CdCr₂S₄ thin films prepared at various deposition potentials: (a) -550 mV versus SCE, (b) -650 mV versus SCE, (c) -750 mV versus SCE and (d) -850 mV versus SCE.

film thickness with deposition time for CdCr₂S₄ thin films prepared at various deposition potentials ranging from -550 to -850 mv versus SCE. It is observed from Fig. 1 that films with lower thickness is obtained at lower potential such as below -750 mV versus SCE. The films prepared at higher potential such as above -750 mV versus SCE thickness of the deposited films decreases due to the process of hydrogen evolution [14]. Hence, the films prepared in the potential region between -550 and -750 mV versus SCE are found to be uniform and dense. It is observed from Fig. 1a that film thickness increases linearly with deposition time tend to attain its maximum value at a deposition time of 45 min. Further increasing deposition time above 45 min thickness of the films remains constant upto 75 min, thereafter it decreases slightly not shown in Fig. 1. Similar trend is noted for films prepared at various potentials. The maximum value of film thickness is obtained for films prepared at a deposition potential -750 mV versus SCE and at a deposition time of 45 min. Similar behaviour exhibited for Cu₂O thin films reported earlier [15].

3.2. Structural studies

3.2.1. Effect of deposition potential

X-ray diffraction pattern recorded for $CdCr_2S_4$ thin films prepared on ITO substrates at various deposition potentials ranging from -550 to -850 mV versus SCE is shown in Fig. 2. X-ray diffraction results represents that the deposited films possess polycrystalline nature with cubic structure with lattice constant (*a* = 10.24 Å)

The diffraction peaks of CdCr₂S₄ are observed at 2θ values of angles 14.82, 24.51, 30.27, 35.12, 43.17, 50.27, 56.72, 68.47, 73.92 corresponding to the lattice planes (111), (220), (222), (400), (422), (440), (642) and (800), respectively. The different peaks in the diffractogram are indexed and the corresponding values of interplanar spacing 'd' are calculated and compared with standard values [16]. It is observed from the diffractogram that all the identified peaks are from CdCr₂S₄ and no additional peaks corresponding to Cd, Cr and S are present. Fig. 2 represents that the degree of crystallinity of the deposited films increases while increasing the deposition potential from -550 to -750 mV versus SCE, thereafter the degree of crystallinity decreases slightly. The height of (220) peak is found to higher than all other peaks in the diffractogram indicates that the crystallites are preferentially oriented



Fig. 3. X-ray diffraction pattern of CdCr₂S₄ thin films prepared at various solution pH values: (a) 3.5 ± 0.1 , (b) 4.5 ± 0.1 , (c) 5.5 ± 0.1 and (d) 6.5 ± 0.1 .

along (220) plane. It is observed from Fig. 2a–c that the height of (220) and all other planes are found to increase while increasing the deposition potential upto –750 mV versus SCE, thereafter the height of all the peaks are decreases slightly as shown in Fig. 2d. The appearance of sharp and more intense diffraction peak at a deposition potential –750 mV versus SCE represents the formation of films with better crystallinity. The crystallite size of the deposited films is calculated using Debye–Scherrer formula given in Eq. (1) [12].

$$D = \frac{0.9\lambda}{\beta \cos \theta_{\rm B}} \tag{1}$$

where λ is wavelength of CuK_{α} target used ($\lambda = 0.1540$ nm), β is Full Width at Half Maximum of the peak in radian, θ_B is Bragg diffraction angle at peak position in degrees. The crystallite size of the films prepared in the potential range between -550 and -850 mV versus SCE are found to be in the range between 32 and 43 nm. Similar behaviour exhibited for Cu₂O thin film reported earlier [15].

3.2.2. Effect of solution pH

The solution pH value is one of the important parameter which determine the structure and stoichiometry of the deposited films. The electrochemical deposition of CdCr₂S₄ thin films are carried out at various solution pH values in the range between 3.5 and 6.5 ± 0.1 . If the solution pH value is lesser than 3.5 ± 0.1 the formation of films may be hindered due to the process of hydrogen evolution reaction. The process of hydrogen evolution gives poor quality films. If the solution pH value is greater than 6.5 ± 0.1 , precipitation of electrolytic bath occurs which in turn yield poor quality films. Hence the solution pH value is fixed in the range between 3.5 and 6.5 ± 0.1 in order to prepare good quality films. X-ray diffraction pattern recorded for CdCr₂S₄ thin films prepared at various solution pH values is shown in Fig. 3. It is observed from Fig. 3 that the diffraction peaks of CdCr₂S₄ are found at values of angles 14.82, 24.51, 30.27, 35.12, 43.17, 50.27, 56.72, 68.47, 73.92 corresponding to the lattice planes (111), (220), (222), (400), (422), (440), (642) and (800), respectively. The different peaks in the diffractogram are indexed and the corresponding values of interplanar spacing 'd' are calculated and compared with standard values [16]. It is observed from Fig. 3a, that the films deposited at pH value around 3.5 ± 0.1 exhibit the peaks of CdCr₂S₄ with preferential orientation along (111) plane. If the pH value of the electrolytic bath is increased



Fig. 4. SEM picture of $CdCr_2S_4$ thin films obtained at a deposition potential of $-750\,mV$ versus SCE.

to 4.5 ± 0.1 the peak height of $(1\ 1\ 1)$ plane decreased and there is slight increment in peak height of $(2\ 2\ 0)$ plane. The films deposited at pH value 5.5 ± 0.1 is found to exhibit well defined crystallites with preferential orientation along $(2\ 2\ 0)$ plane. Further increasing the pH value above 5.5 ± 0.1 , the intensity of all the peaks are found to decrease as shown in Fig. 3d. It is also observed from Fig. 3a–d there is no change in crystal structure, but there is change in preferential orientation of the plane from 3.5 ± 0.1 to 5.5 ± 0.1 is observed. Similar behaviour is exhibited for Cu₂O thin films reported earlier [17]. Hence, the solution pH value is fixed as 5.5 ± 0.1 for further studies. The sizes of the crystallites are found to be in the range between 20 and 43 nm for films obtained at different pH values.

3.3. Morphological and compositional analyses

The surface morphology of CdCr₂S₄ thin films has been analyzed using scanning electron microscope. Fig. 4 shows the SEM image of CdCr₂S₄ thin films prepared at a deposition potential -750 mV versus SCE. It is observed from Fig. 4 that the film surface is found to be smooth and covered with tiny spherically shaped grains. The grains are distributed over the entire surface of the film. The unreacted sulphur could be seen at few places on the surface of the film. The sizes of the grains are found to be in the range between 0.12 and 0.22 μ m. The average size of the grains is found to be 0.16 μ m.

The quantitative analysis of CdCr₂S₄ thin films has been carried out in order to determine the relationship between deposition potential and film composition. After etching the film surface, a quantitative determination of CdCr₂S₄ thin films has been analyzed using energy dispersive analysis by X-ray spectroscopy. Fig. 5 shows the variation of Cd, Cr and S content with deposition potential for CdCr₂S₄ thin films obtained at various deposition potentials. It is observed from Fig. 5 that the content of Cd and S decreases and the content of Cr increases while increasing the deposition potential from -550 to -850 mV versus SCE. The atomic molar ratio (Cd:Cr:S) for CdCr₂S₄ thin films obtained at deposition potential -750 mV versus is found to be 1.09:1.83:4.08: indicates the nearly stoichiometric formation of CdCr₂S₄ thin films. This result is consistent with X-ray diffraction analysis of the sample with phase corresponds to CdCr₂S₄. Similar result exhibited for CdCr₂S₄ films reported earlier [7].

3.4. Optical properties

The optical absorption of $CdCr_2S_4$ thin films has been analyzed without accounting for reflection and transmission losses. The nature of transition involved is determined from



Fig. 5. Variation of Cd, Cr and S content with deposition potential for films obtained at various deposition potentials.



Fig. 6. Plot of hv versus $(\alpha hv)^2$ for CdCr₂S₄ thin films prepared at a deposition potential of -750 mV versus SCE.

the absorption coefficient values using the following relation [14].

$$\alpha h \nu = A (h \nu - E_{\rm g})^n \tag{2}$$

where α is the absorption coefficient in cm⁻¹, $h\nu$ is the photon energy, A is an energy dependent constant and E_{g} is the energy gap. For allowed direct transition n = 1/2 and for allowed indirect transition n = 2. From the calculated values of absorption coefficients, a plot of hv versus $(\alpha hv)^2$ is drawn for CdCr₂S₄ thin film prepared at a potential value -750 mV versus SCE and shown in (Fig. 6). The linear portion of the graph is extrapolated to the energy axis (X-axis) which is shown in Fig. 6. The intersection point gives the band gap energy of the material. The estimated value of band gap is found to be 2.38 eV. The band gap value of material obtained in this work is quite closer to the value reported earlier [7]. The refractive index and extinction coefficient are calculated for films obtained at a deposition potential -750 mV versus SCE in the wavelength range between 350 and 1100 nm. Fig. 7 shows the variation of refractive index and extinction coefficient with wavelength for CdCr₂S₄ thin films. It is observed from



Fig. 7. Variation of refractive index (*n*) and extinction coefficient (*k*) with wavelength (λ) for CdCr₂S₄ thin films.

Fig. 7 that the value of refractive index increases and extinction coefficient decreases upto 530 nm, thereafter both of them increases.

4. Conclusions

Thin films of $CdCr_2S_4$ have been deposited on ITO substrates at various deposition potential and solution pH values using potentiostatic electrodeposition technique. X-ray diffraction pattern of the deposited films reveals the formation of films with polycrystalline nature with tetragonal structure. It is also observed that the crys-tallites are found to exhibit most prominent reflection along (2 2 0) plane. The pH effect on structural properties shows that there is change in most prominent reflection from (1 1 1) to (2 2 0) for films obtained at various solution pH values. Surface morphology and film composition shows that films with better quality and stoichiometry are obtained at a deposition potential -750 mV versus SCE. The band gap value of the material obtained is this work is found to be 2.38 eV which is in close agreement with the value reported earlier. The value refractive index and extinction coefficient are found to 2.6 and 0.017.

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